

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|---|------------------|---------|------------------|
| L1 | 5 | (semiconductor and power and substrate and voltage and sustain\$3 and trench and column and diffus\$3 and sidewall and adjacent and vertical\$3 and fill\$3 and junction).clm. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/03/15 16:58 |
| L2 | 6 | (semiconductor and power and substrate and voltage and sustain\$3 and trench and barrier and etch\$3 and fill\$3 and diffus\$3 and overlap\$4).clm. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2006/03/15 17:00 |